

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Pan et al.

Serial No.: 09/614,113

Filed: July 12, 2000

For: METHODS OF FORMING A GATE STACK THAT IS VOID OF SILICON CLUSTERS WITHIN A METALLIC SILICIDE FILM THEREOF (as amended)

Confirmation No.: 1710

Examiner: D. Deo

Group Art Unit: 1765

Attorney Docket No.: 2269-2915.3US

(96-0149.02/US)

Notice of Allowance Mailed:

July 11, 2003

Express Mail Mailing Label No.:

EV 326922977 US

Date of Deposit with USPS:

October 9, 2003

Person making Deposit: Christopher Haughton

AMENDMENT PURSUANT TO 37 C.F.R. § 1.312(a)

Mail Stop ISSUE FEE Commissioner for Patents P.O. Box 1450 Alexandria, Virginia 22313-1450

Sir:

Please amend the above-referenced application as follows:

Amendments to the Title appear on page 3 of this paper.

Amendments to the Specification appear on page 4 of this paper.

Amendments to the Claims are reflected in the listing of claims which begins on page 5 of this paper.

Amendments to the Drawings appear on page 8 of this paper and include both an attached replacement sheet and an annotated sheet showing changes.

Remarks begin on page 9 of this paper.

An **Appendix** including amended drawing figures is attached following page 9 of this paper.